

John Bardeen\*\*, William B. Shockley und Walter Brattain (v.l.n.r., 1956) erfanden den bipolaren Transistor 1947 in den Bell Laboratories

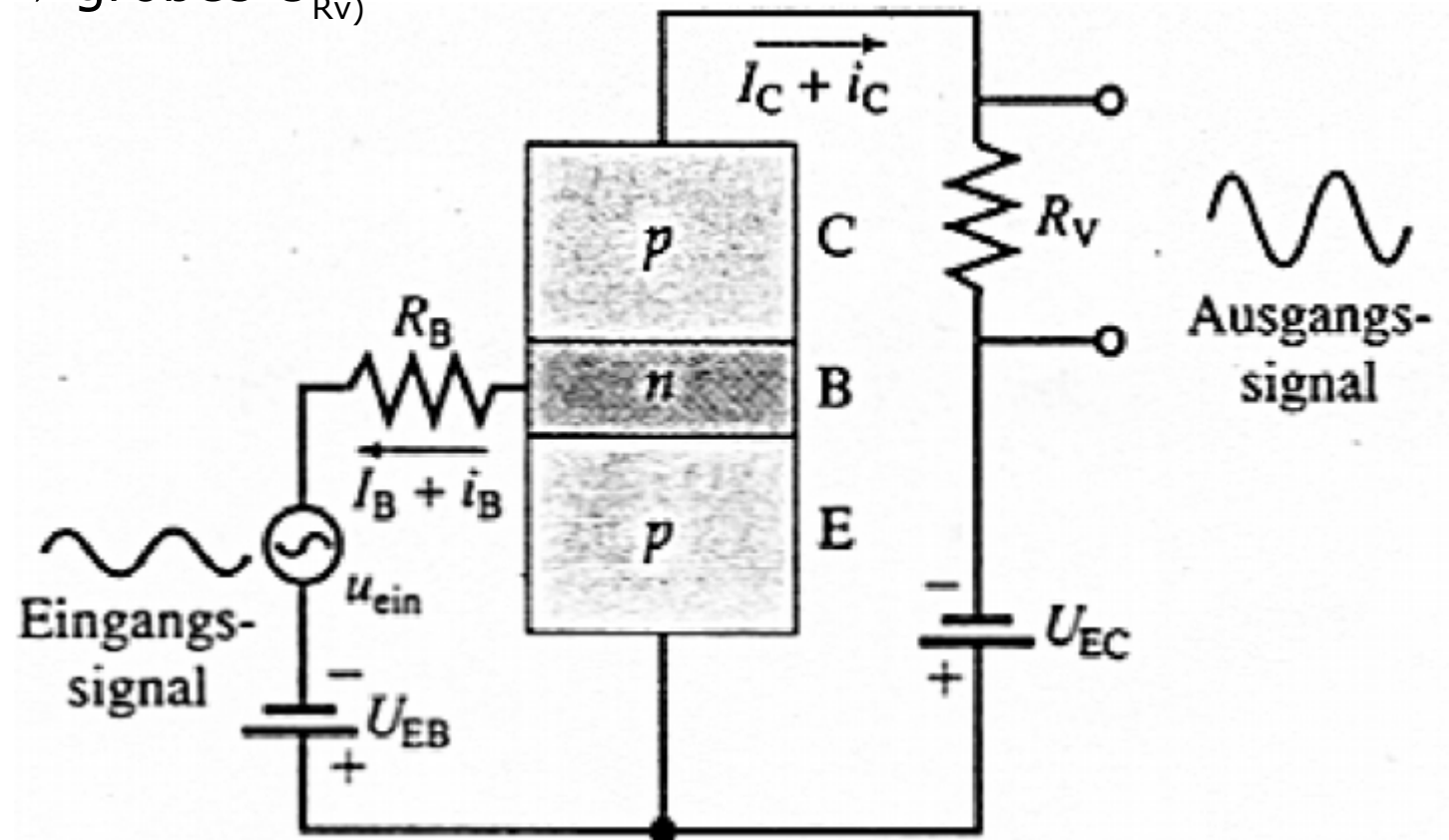
Originalversuchsaufbau (Quelle: Lucent Technologies)

# pnp-Transistorverstärkerschaltung

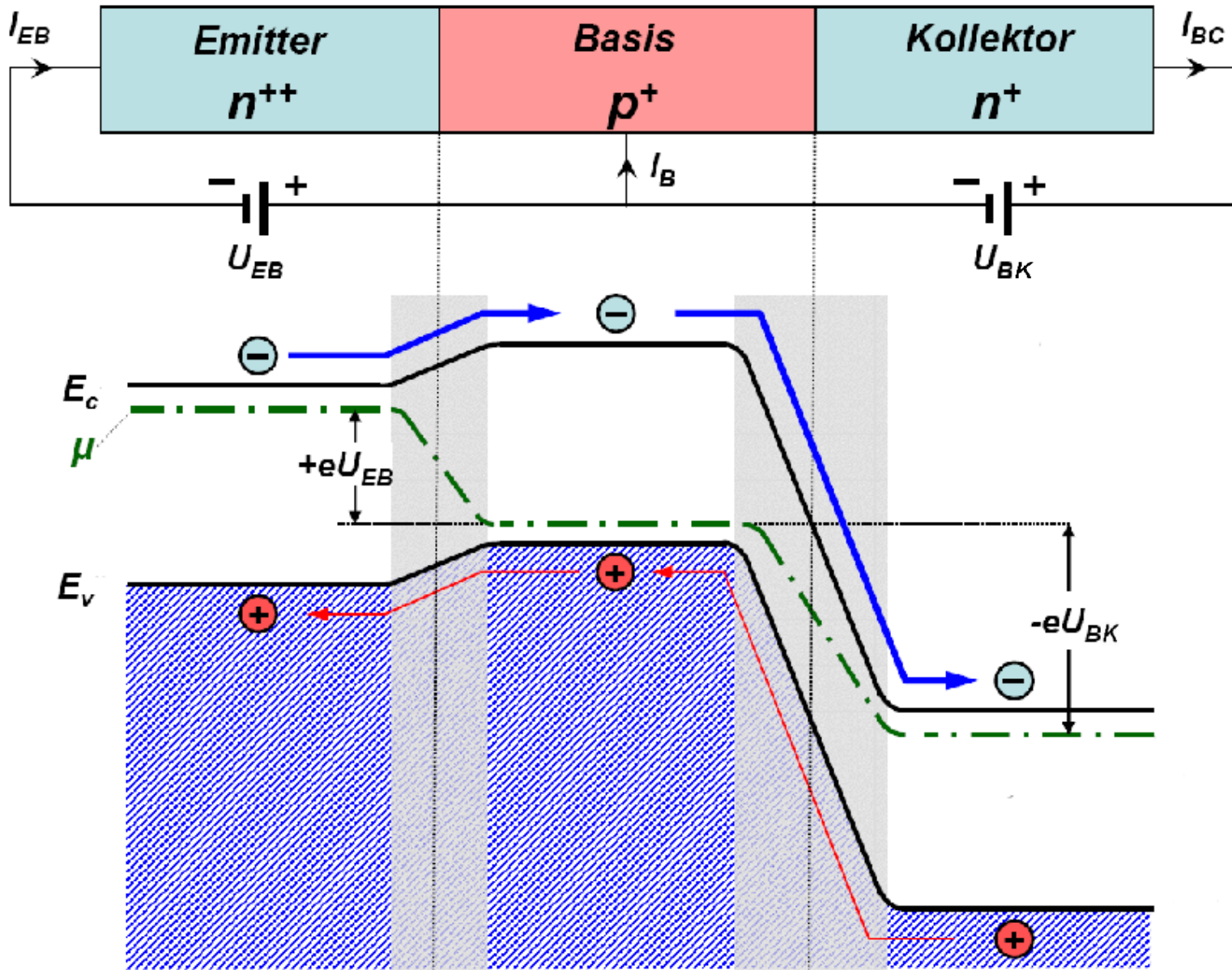
kleine Änderung  $i_B$  des Basisstroms  $I_B$

→ große Änderung  $i_c$  des Kollektorstroms  $I_c$

(oder: kleines  $u_{\text{ein}}$  → großes  $U_{Rv}$ )



# nnn-Transistor



EB in Durchlass-, BK in Sperrrichtung; Basis dünn gegen Diffusionslänge; über EB injizierte Ladungsträger diffundieren (transistor!) zu K; dort durch Sperrspannung abgesaugt

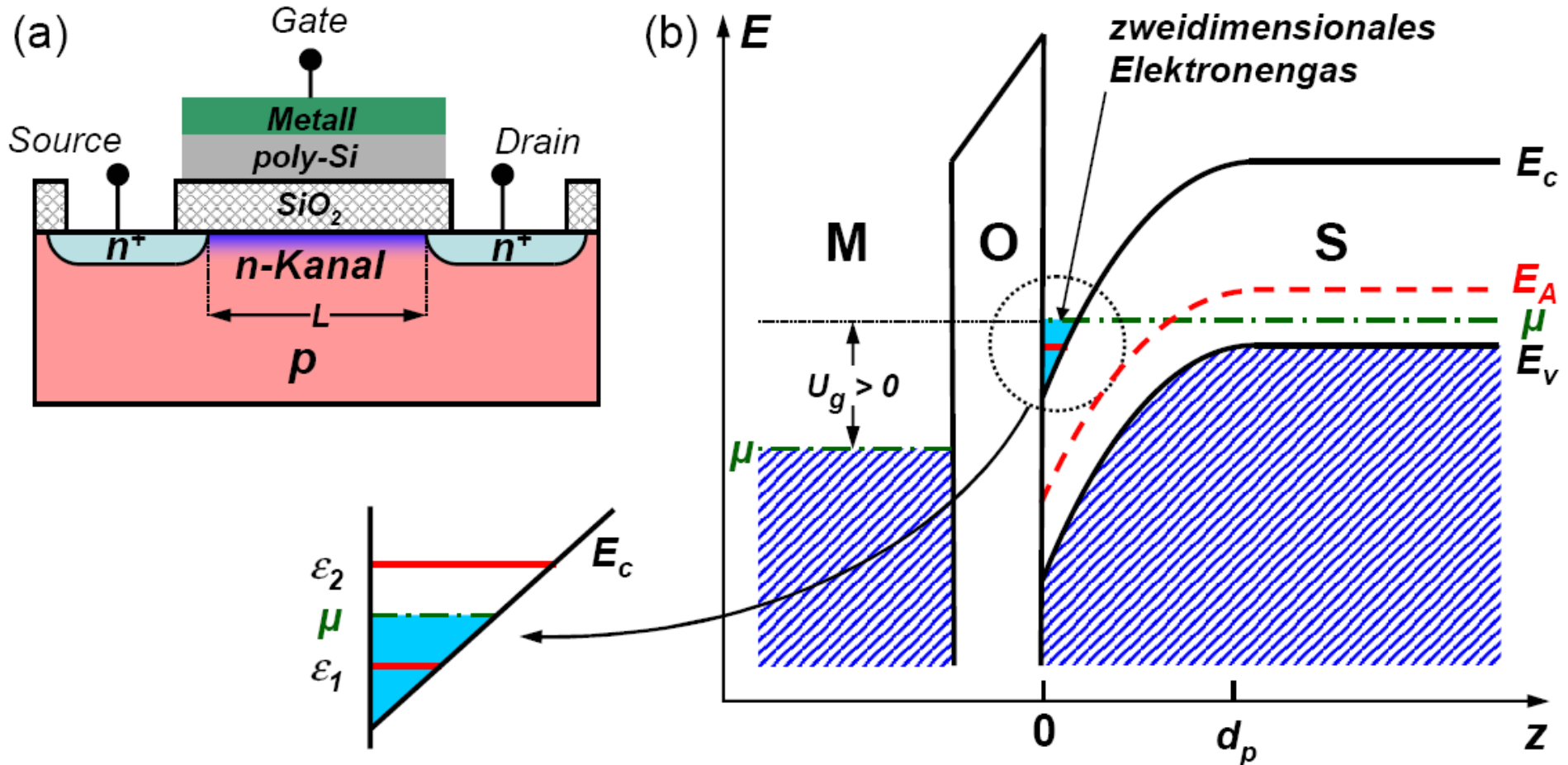
n.b.: dicke Basis hat Strom 0 zur Folge

# MOSFET

Metal-Oxide-Semiconductor Field Effect Transistor (1960)

Julius E. Lilienfeld, U.S. Patent 1, 745, 175 (1930)

Oskar Heil, British Patent 439, 457 (1935)



MOSFET Gate-Spannung  $U_g > 0$

Gate-Feld hält Elektronen im Kanal

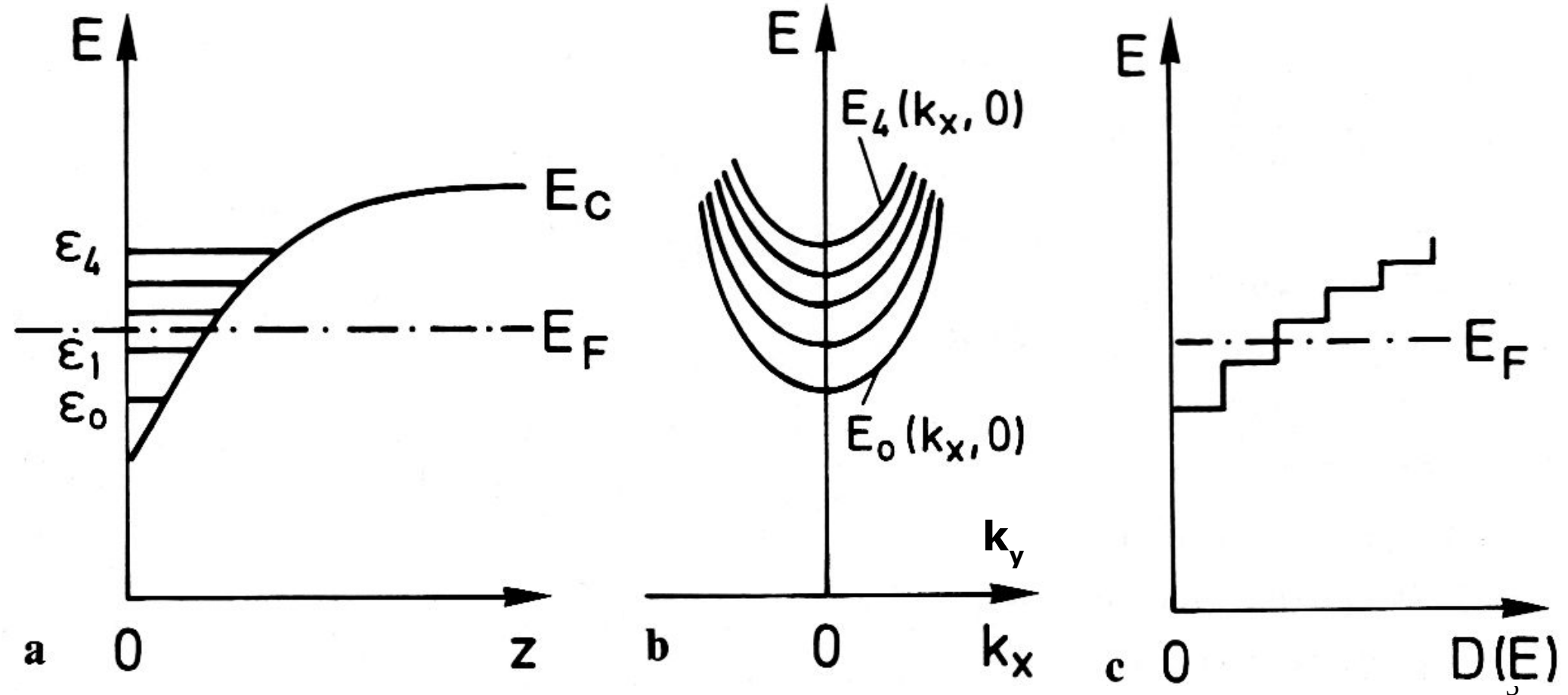
Dreieckspotenzial an Grenzfläche p-Halbleiter/Oxidschicht: 2DEG

hier unterstes Subband besetzt

"Nebeneffekt":

# Niedrigdimensionale Elektronensysteme

Quantentrog (quantum well)





# Andere Realisierung: Heterostrukturen

Binäre Verbindungen: GaAs 2- oder Mehrlagensysteme

Ternäre Verbindungen:  $\text{Al}_x\text{Ga}_{1-x}\text{As}$

Quaternäre Verbindungen:  $\text{Ga}_x\text{In}_{1-x}\text{As}_y\text{P}_{1-y}$

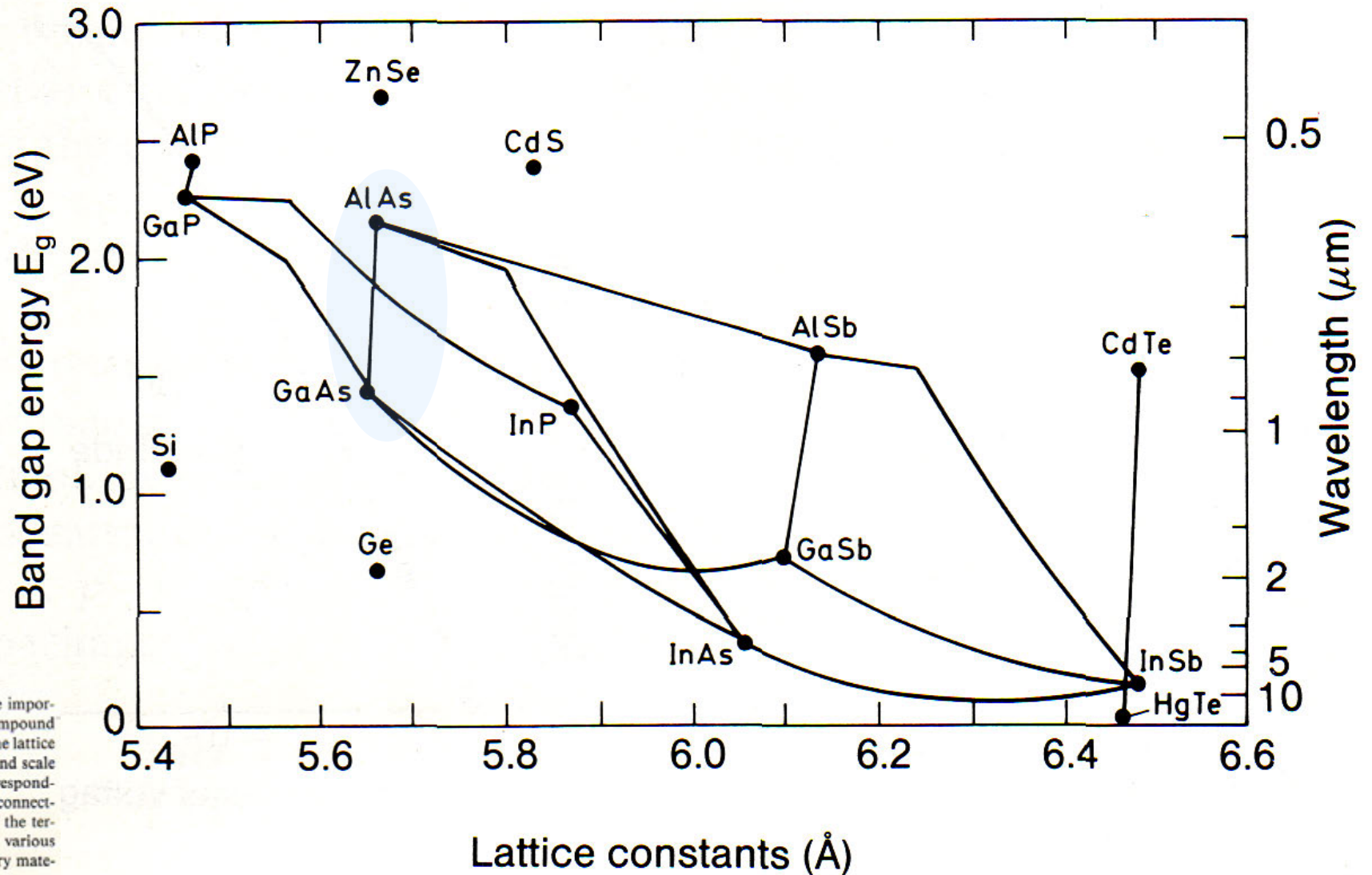
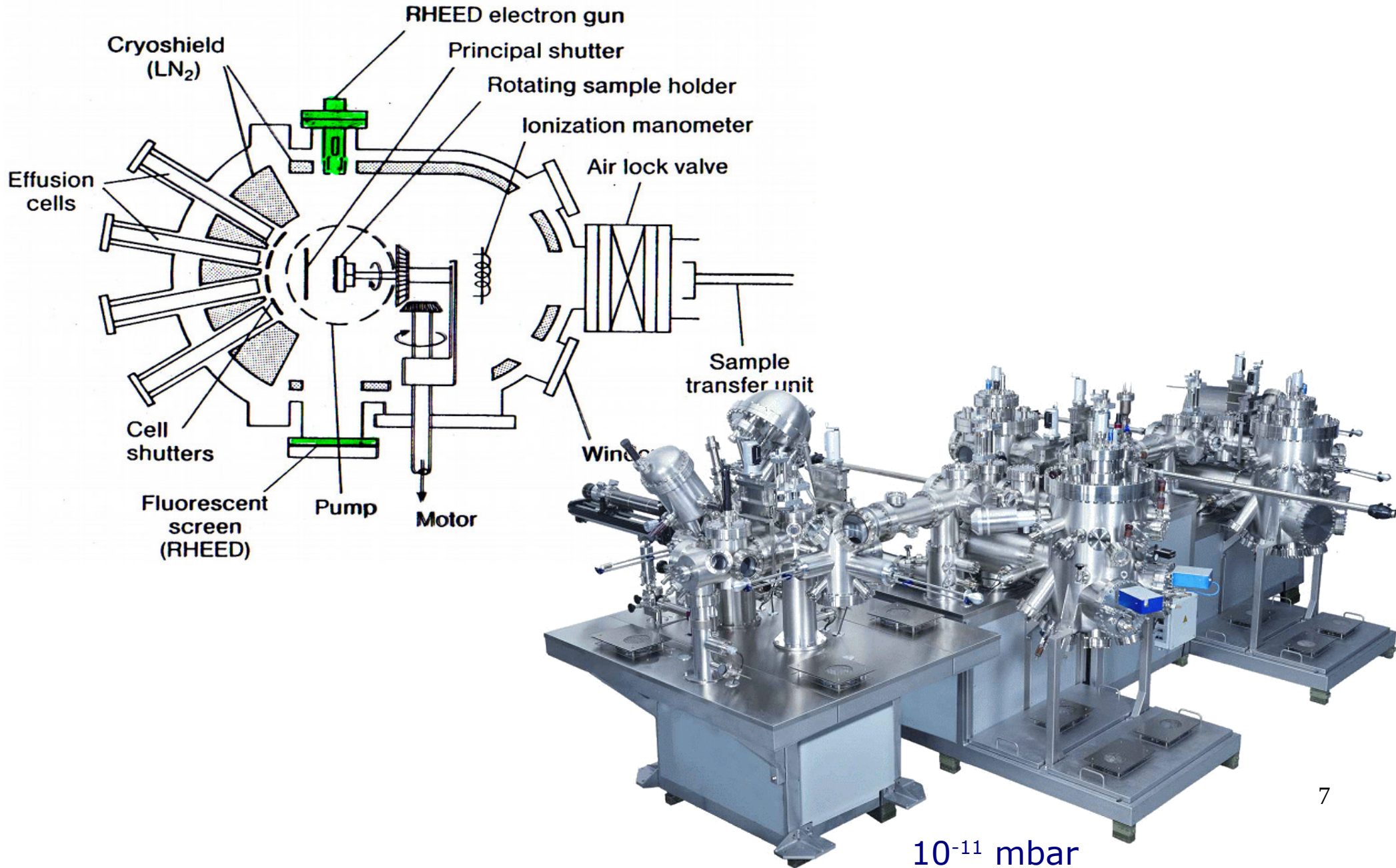


Fig. 12.21. Band gap  $E_g$  of some important elemental and binary compound semiconductors plotted against the lattice parameter at 300 K. The right-hand scale gives the light wavelength  $\lambda$  corresponding to the band gap energy. The connecting lines give the energy gaps of the ternary compounds composed of various ratios of the corresponding binary materials

# Molekularstrahlepitaxie (MBE)

Metal Organic Chemical Vapour Deposition (MOCVD)



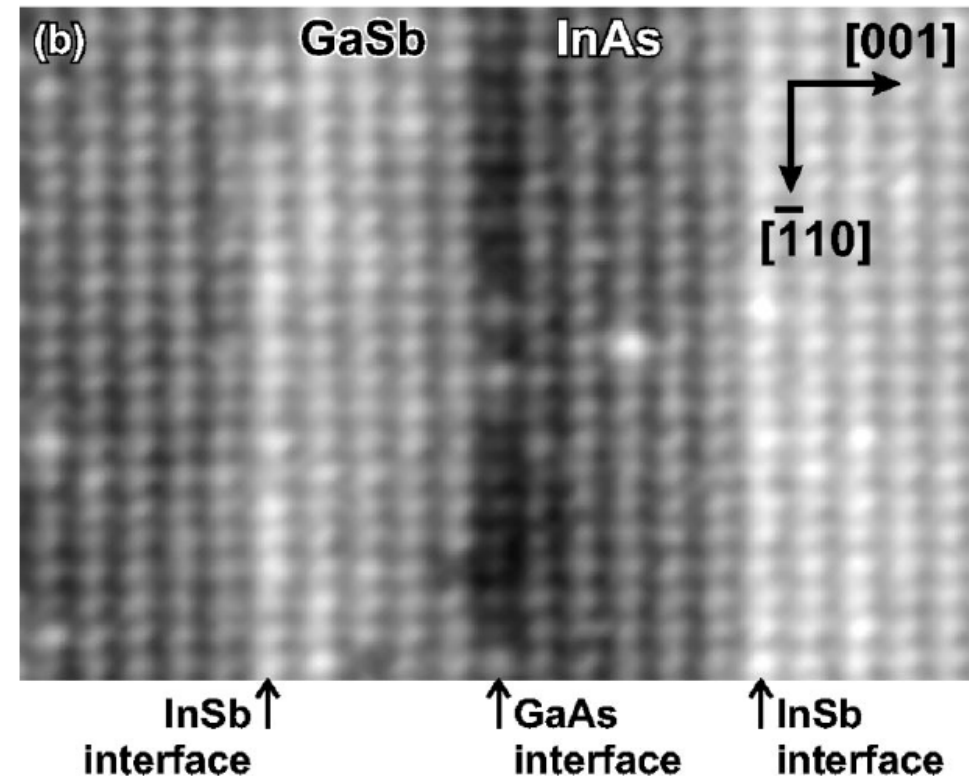
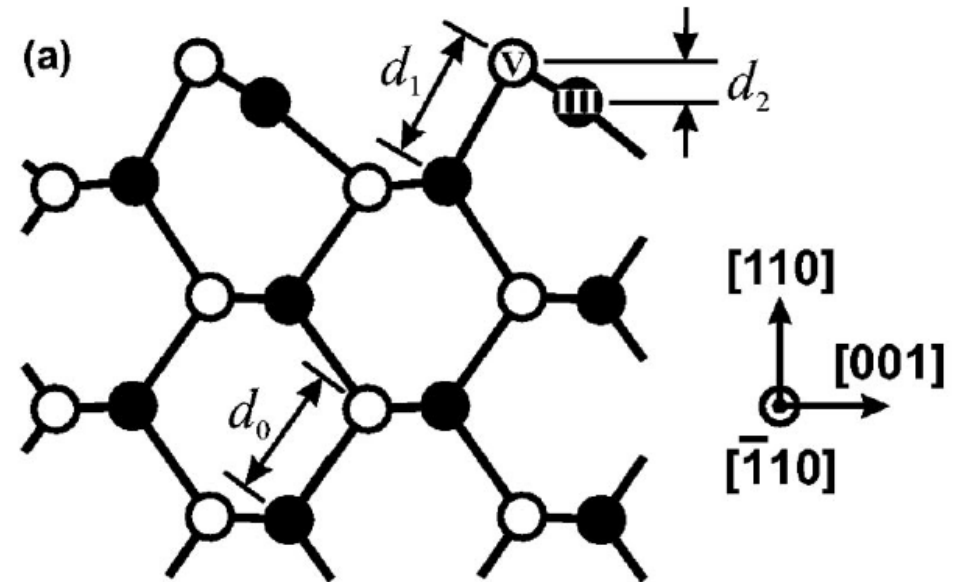
# Ausdehnung der Übergangszone ?

Strukturell: 1 Atomlage

Elektronisch:

Bandlücke 1 Atomlage

Bandverbiegung  $\lambda_D$  ( $\approx 10$  nm)



PHYSICAL REVIEW B 67, R121306 (2003)

(a) Relaxed geometry of a III-V (110) surface.

$d_0$ : bond length in the bulk

$d_1$ : surface III-V bond length indicated

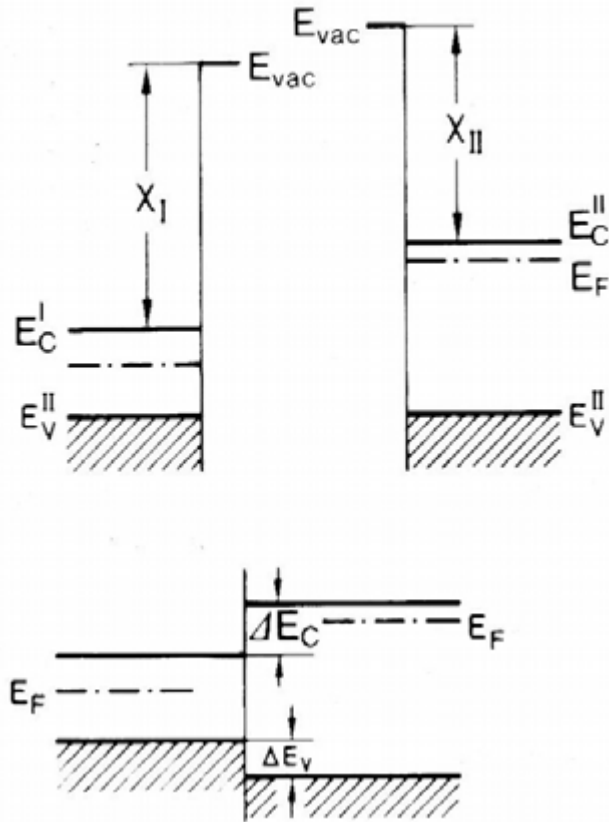
$d_2$ : III-V height difference at surface

(b) Constant-current, filled-state STM image of

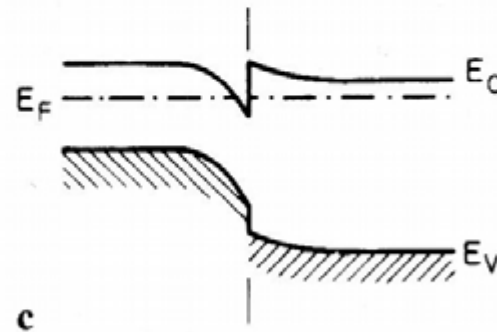
InAs/GaAs superlattice



Semiconductor I Semiconductor II



Im Gleichgewicht:



**Fig. 12.22 a–c.** Band schemes (one-electron energies plotted in real space) for a heterostructure formed from semiconductors I and II. **a** Semiconductors I and II are assumed to be isolated;  $\chi_I$  and  $\chi_{II}$  are the electron affinities, i.e., the energy between the vacuum energy  $E_{vac}$  and the lower conduction band edge  $E_C$ . **b** Semiconductors I and II are in contact, but not in thermal equilibrium because the Fermi levels  $E_F$  on the two sides have not equalized.  $\Delta E_C$  and  $\Delta E_V$  are the band discontinuities in the conduction and valence bands, respectively. **c** In thermal equilibrium, the Fermi energies  $E_F$  in I and II must be identical. Since the band discontinuities  $\Delta E_C$  and  $\Delta E_V$  are predetermined, band bending must occur in the two semiconductors

$\chi$  Elektronenaffinität

Leitungsbanddiskontinuität  $\Delta E_C = \chi_1 - \chi_2$

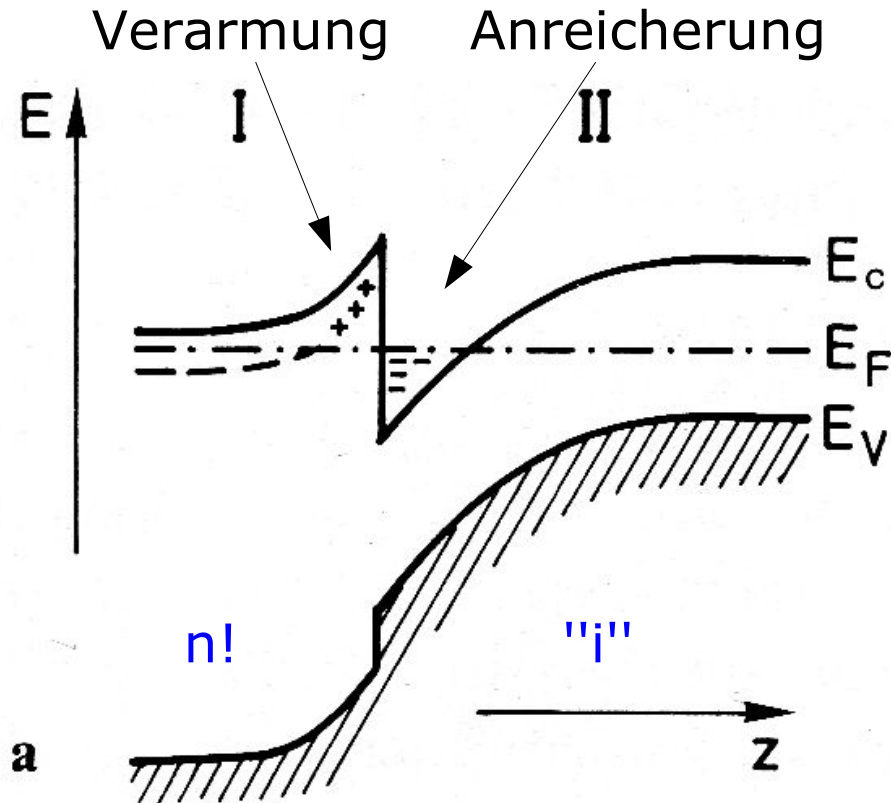
(Obacht: Oberflächendipol, Defekt/Grenzflächenzustände)

# Modulation doping

N-n heterojunction

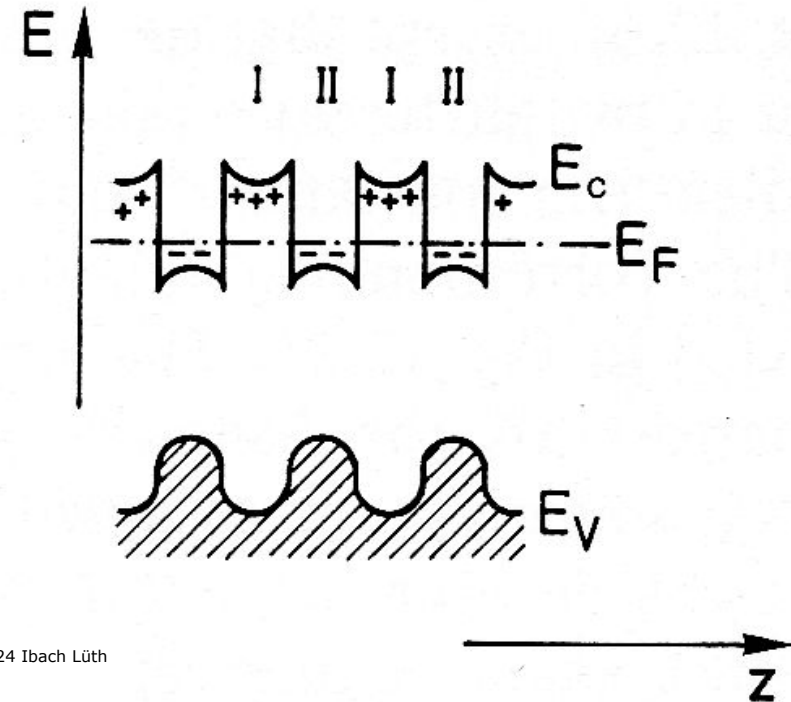
I: wide gap heavily n-doped

II: narrower gap weakly n-doped

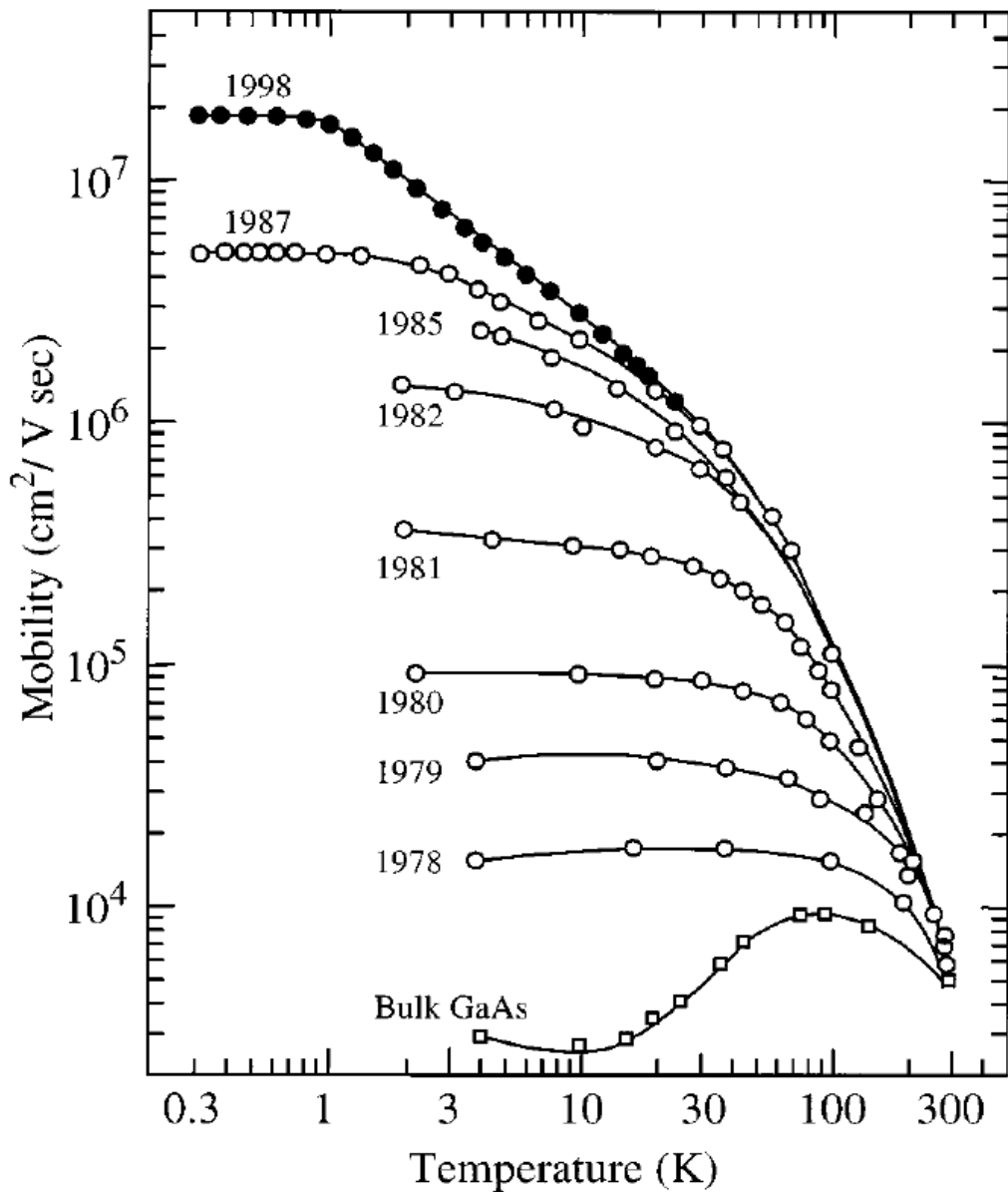


Electrons confined against AlGaAs by E-field of dopants ( $\text{Si}^+$ )

band scheme of superlattice



# Electron mobility of 2DEGs in modulation doped GaAs/AlGaAs



high T / lowest T:  $\mu$  limited by scattering from phonons / defects

Progress made: Thousandfold increase of  $\mu$  through modulation doping.

$\mu = 2 \times 10^7 \text{ cm}^2/\text{Vs}$  corresponds to 1/5 mm ballistic electron motion between collisions

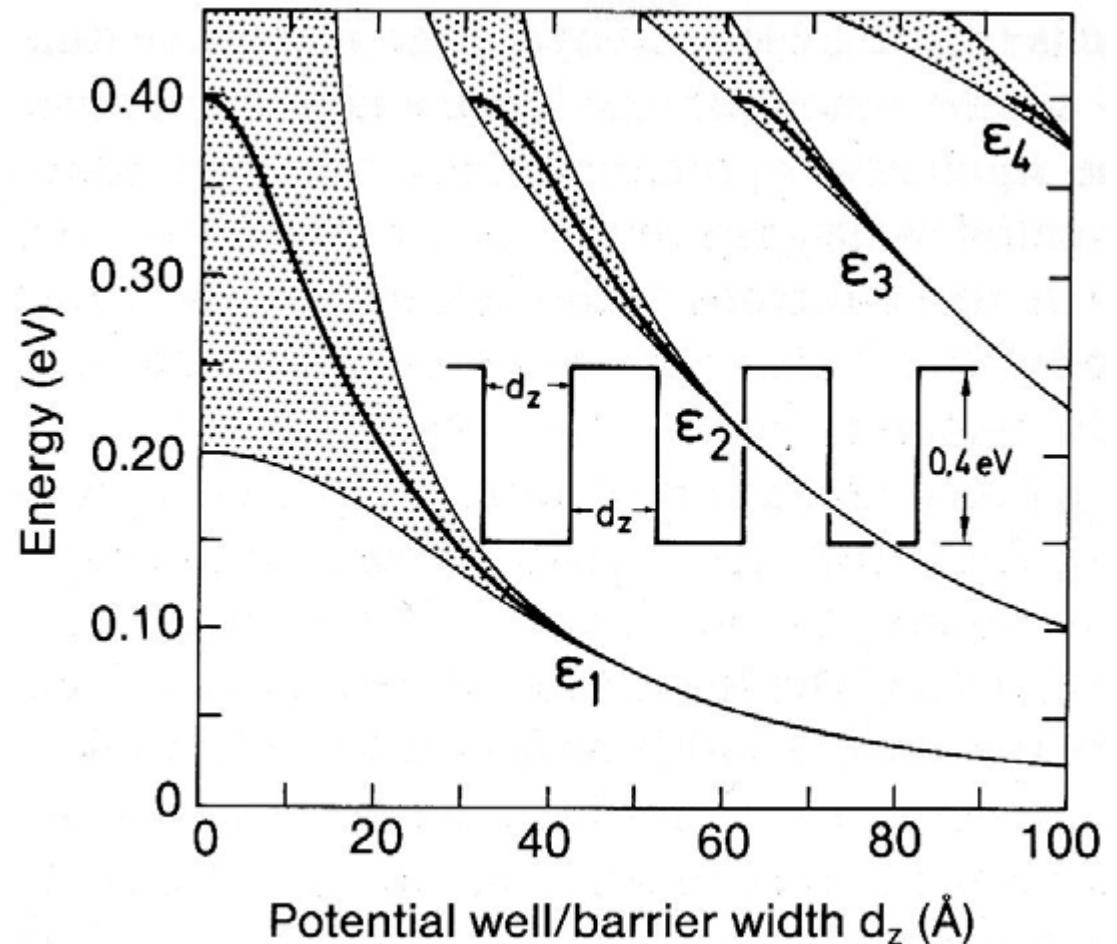


Inventors of the modulation-doping process, in 1978 around an early MBE machine at Bell Labs. From left: Willy Wiegmann, Art Gossard, Horst Störmer, Ray Dingle

HEMT

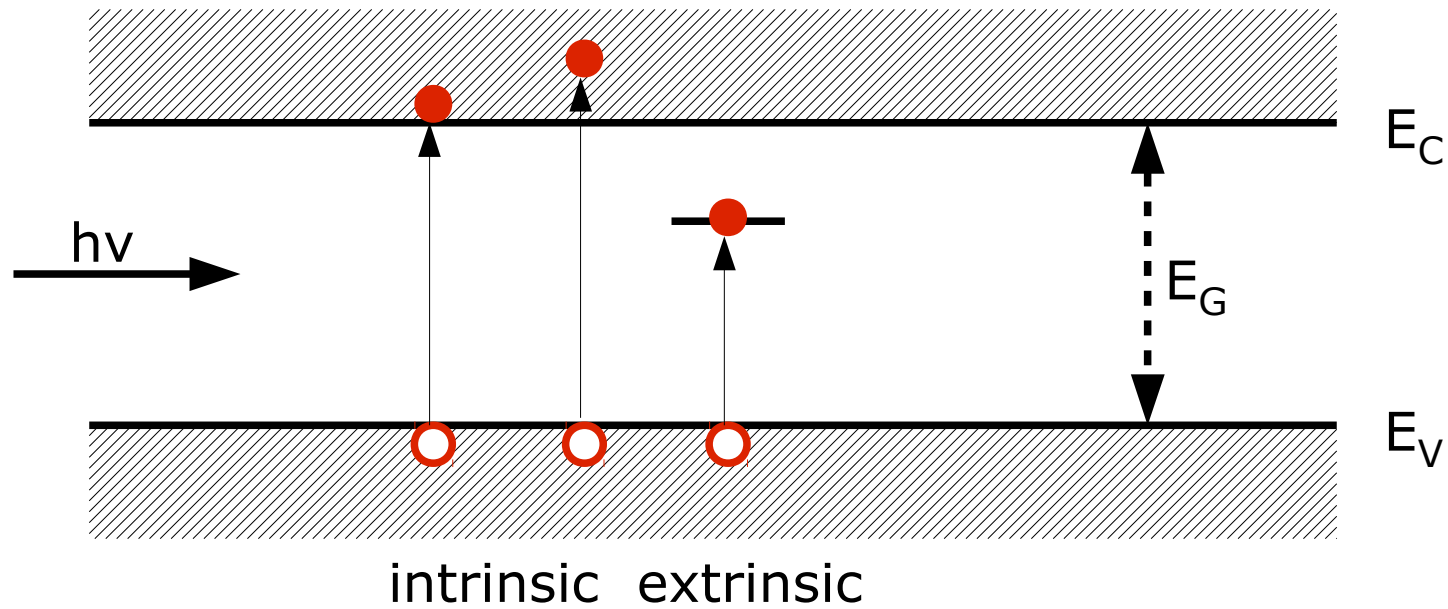
# Superlattices

**Fig. 12.27.** Energy states of electrons confined in the rectangular potential wells (inset) of the conduction bands of a composition superlattice; the potential wells have a width  $d_z$  which also corresponds to their distance from one another. For the calculation, an electronic effective mass of  $m^* = 0.1 m_0$  was assumed. The heavy lines in the shaded regions are the results for single potential wells with the corresponding widths  $d_z$ ; potential wells in a superlattice with sufficiently small separation lead to overlap of wavefunctions and therefore to a broadening into bands (*shaded region*). (After [12.7])





# Light Absorption in Semiconductors

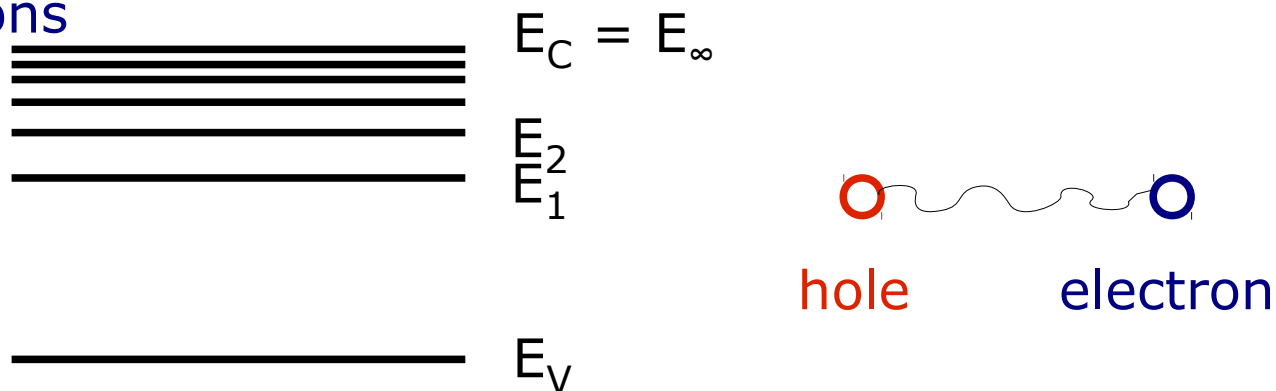


## Luminescence

Photoluminescence

Cathodoluminescence; Minority injection, Impact Ionization

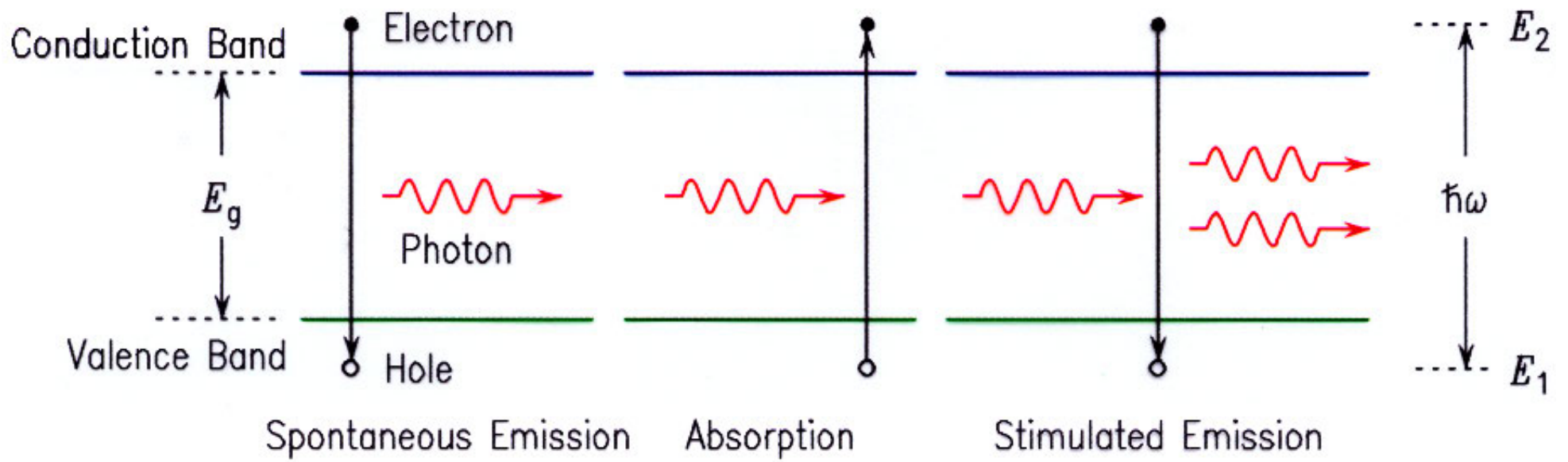
## Excitons



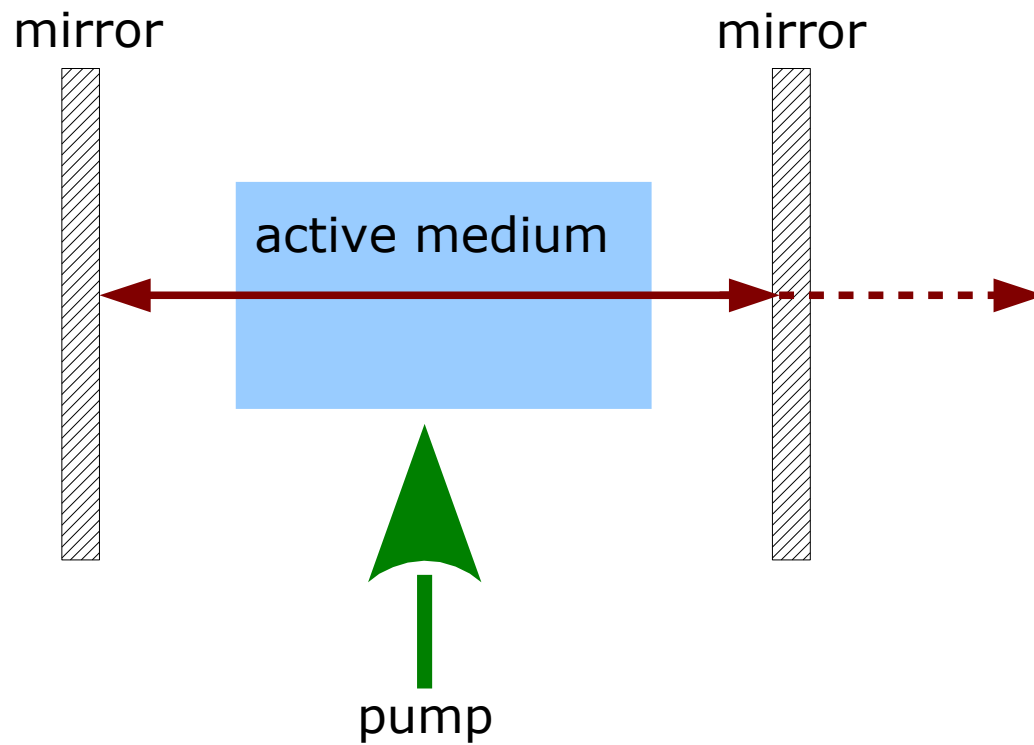
# LED – Light Emitting Diode

diode at forward bias – recombination – radiation

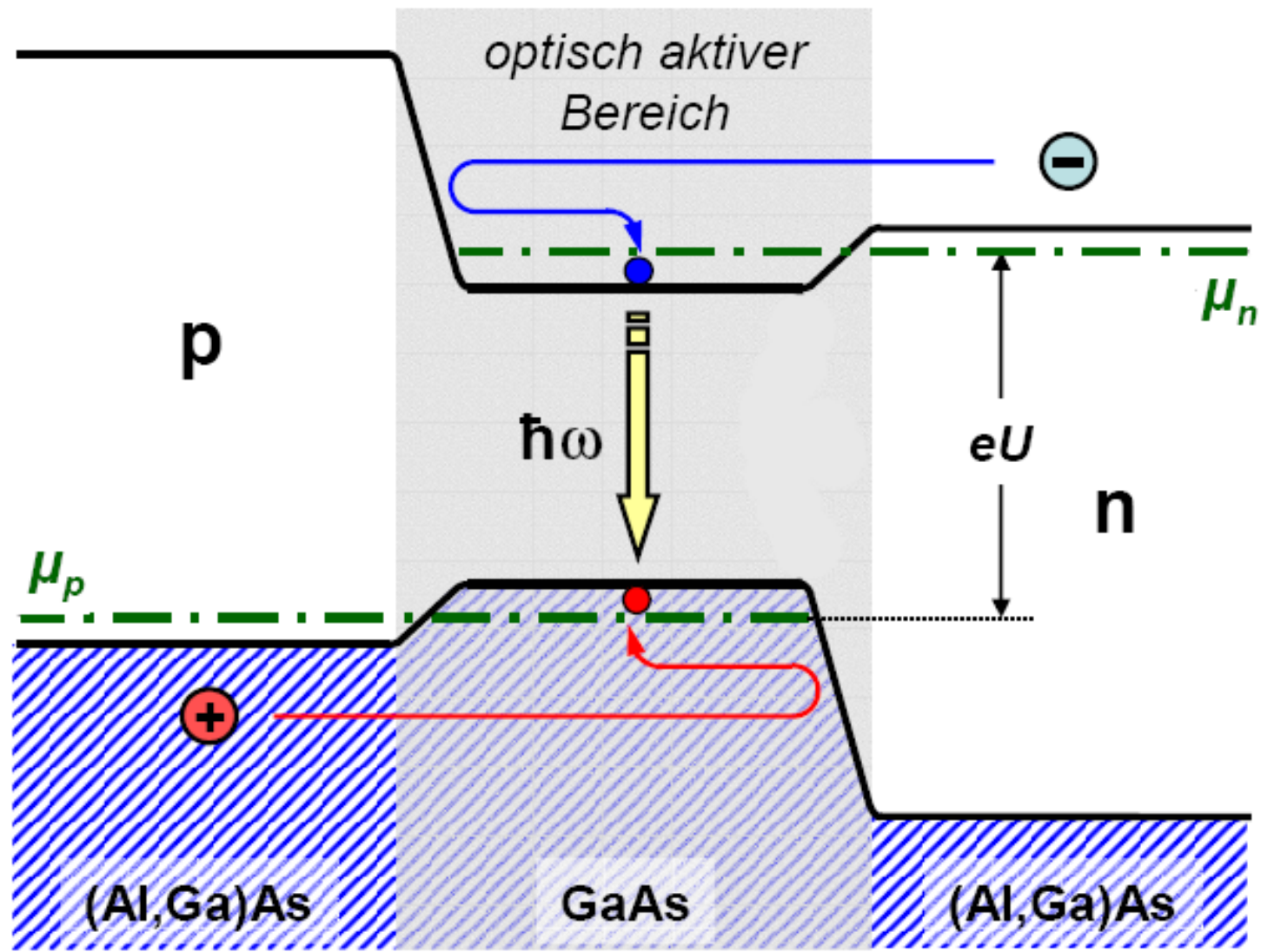
GaAs	1.43 eV	870 nm	IR communication
GaP	2.26 eV	550 nm	green LED
$\text{GaAs}_x\text{P}_{1-x}$	variable		red LED
GaN	3.4 eV	405 nm	violet LED
$\text{In}_x\text{Ga}_{1-x}\text{N}$	variable		blue LED



Laser

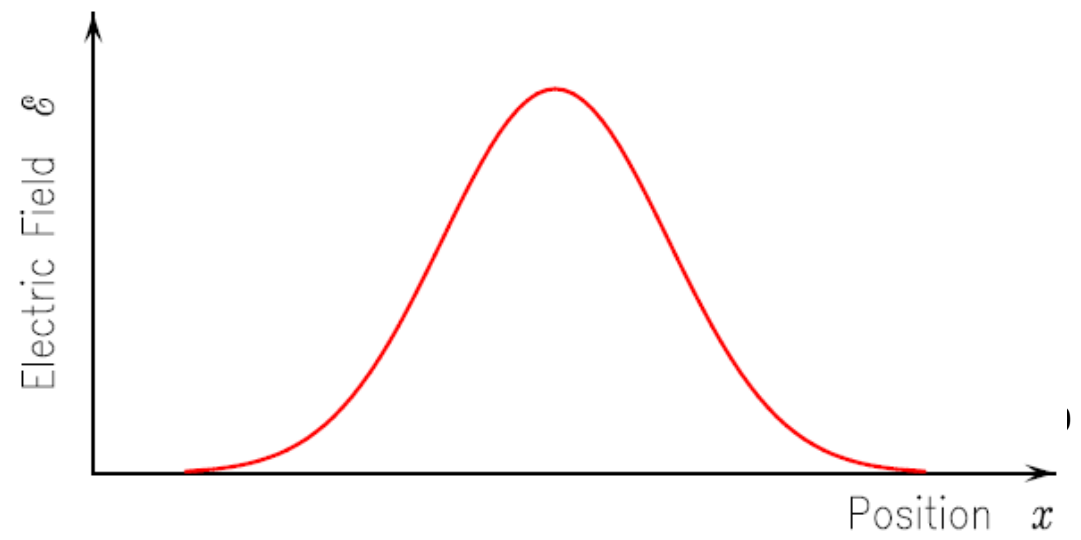
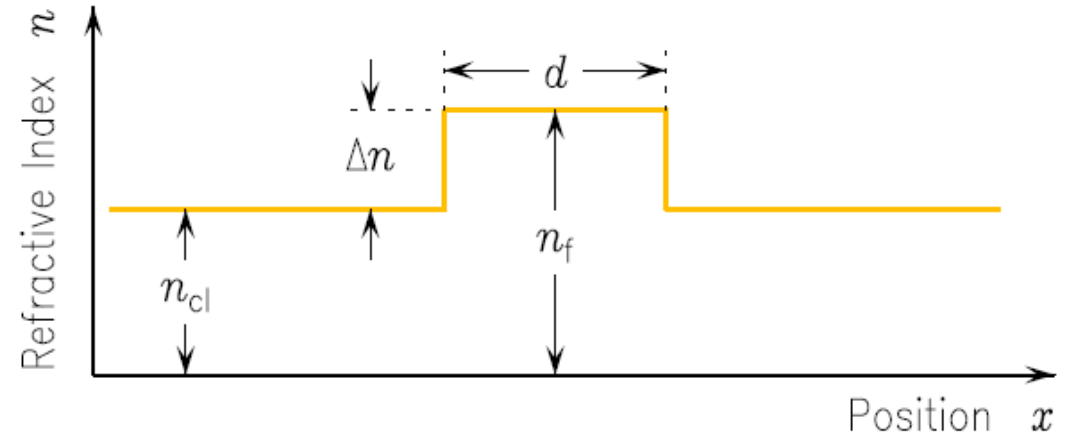
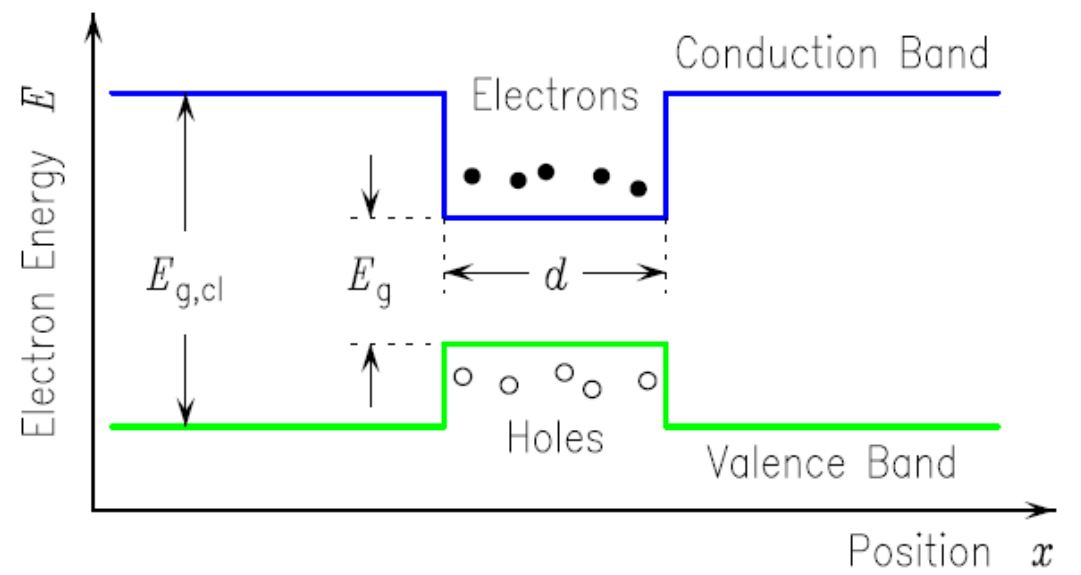


# Halbleiterlaser

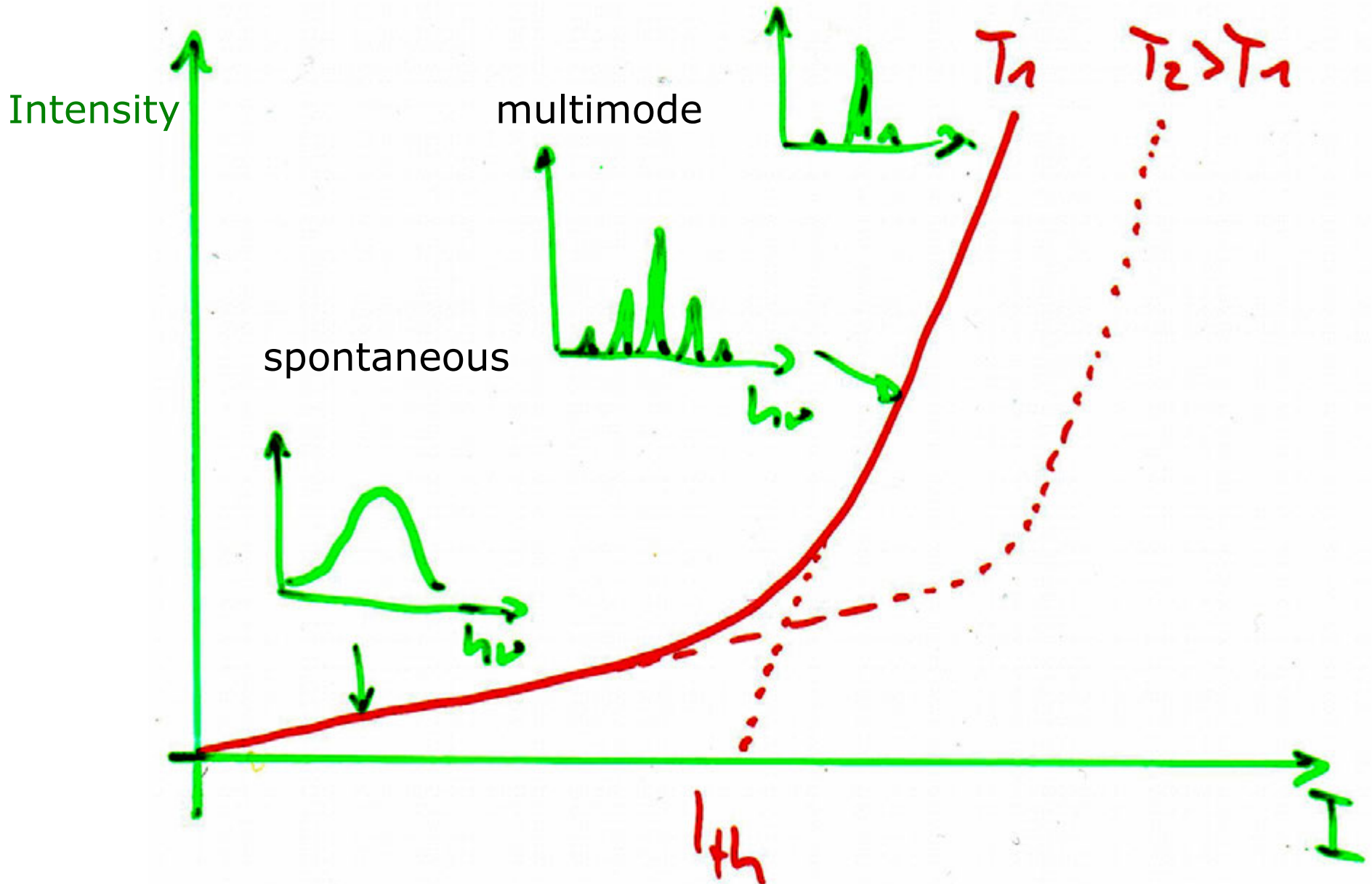




# Halbleiterlaser

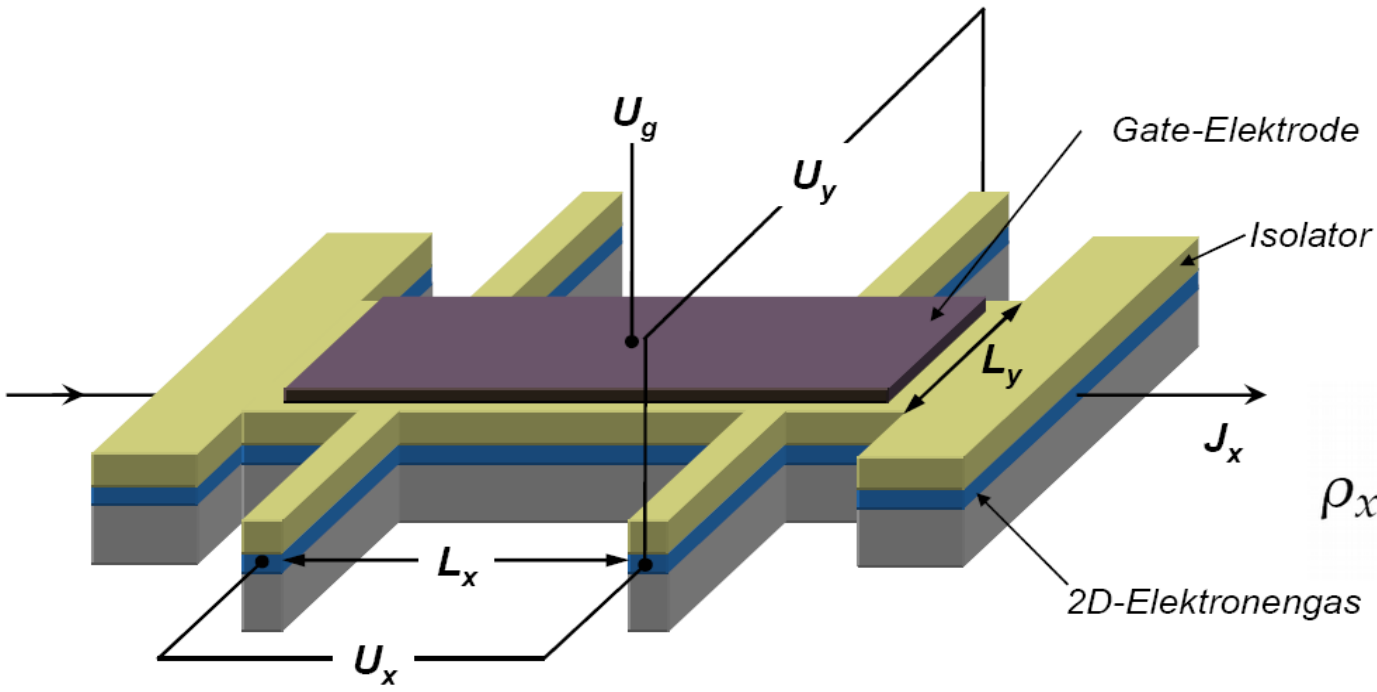


Resonator provides many standing wave modes  
singlemode



POPULARISING your science may lead to a terminal loss of serious reputation. So why not go for broke--as have the authors of "Britney's Guide to Semiconductor Physics"? As you can read at <http://britneyspears.ac/lasers.htm>, "It is a little known fact that Ms Spears is an expert in semiconductor physics. Not content with just singing, in the following pages, she will guide you in the fundamentals of the vital laser components that have made it possible to hear her super music in a digital format."

# Halleffekt an 2D Elektronengasen



$$\rho_{xy} = \frac{B}{n_{2D}e} = R_H \cdot B$$

$$\begin{pmatrix} J_x \\ J_y \end{pmatrix} = \frac{\sigma_0}{1 + \omega_c^2 \tau^2} \begin{pmatrix} 1 & +\omega_c \tau \\ -\omega_c \tau & 1 \end{pmatrix} \begin{pmatrix} E_x \\ E_y \end{pmatrix}$$

$$\sigma_0 = \frac{n_{2D}e^2\tau}{m^*}$$

$$\omega_c = \frac{eB}{m^*}$$

$$\rho_{xx} = \frac{\sigma_{xx}}{\sigma_{xx}^2 + \sigma_{xy}^2}$$

$$\rho_{xy} = \frac{-\sigma_{xy}}{\sigma_{xx}^2 + \sigma_{xy}^2}$$

$$\rho_{yy} = \rho_{xx}$$

$$\rho_{yx} = -\rho_{xy}$$

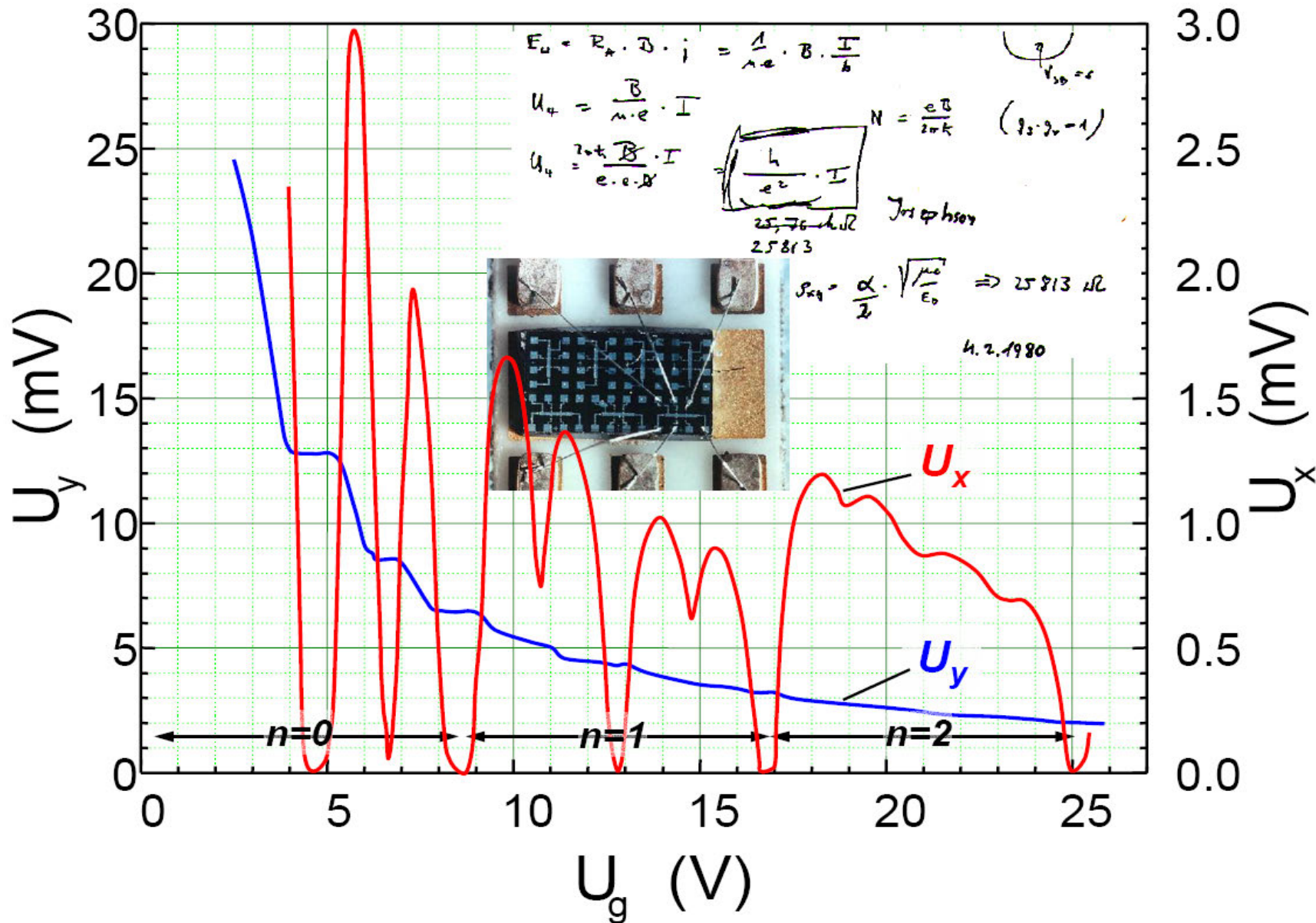
$$\begin{aligned} \sigma_{xx} &= \frac{\rho_{xx}}{\rho_{xx}^2 + \rho_{xy}^2} & \sigma_{xy} &= \frac{-\rho_{xy}}{\rho_{xx}^2 + \rho_{xy}^2} \\ \sigma_{yy} &= \sigma_{xx} & \sigma_{yx} &= -\sigma_{xy} \end{aligned}$$



# Ganzahliger Quanten-Hall-Effekt



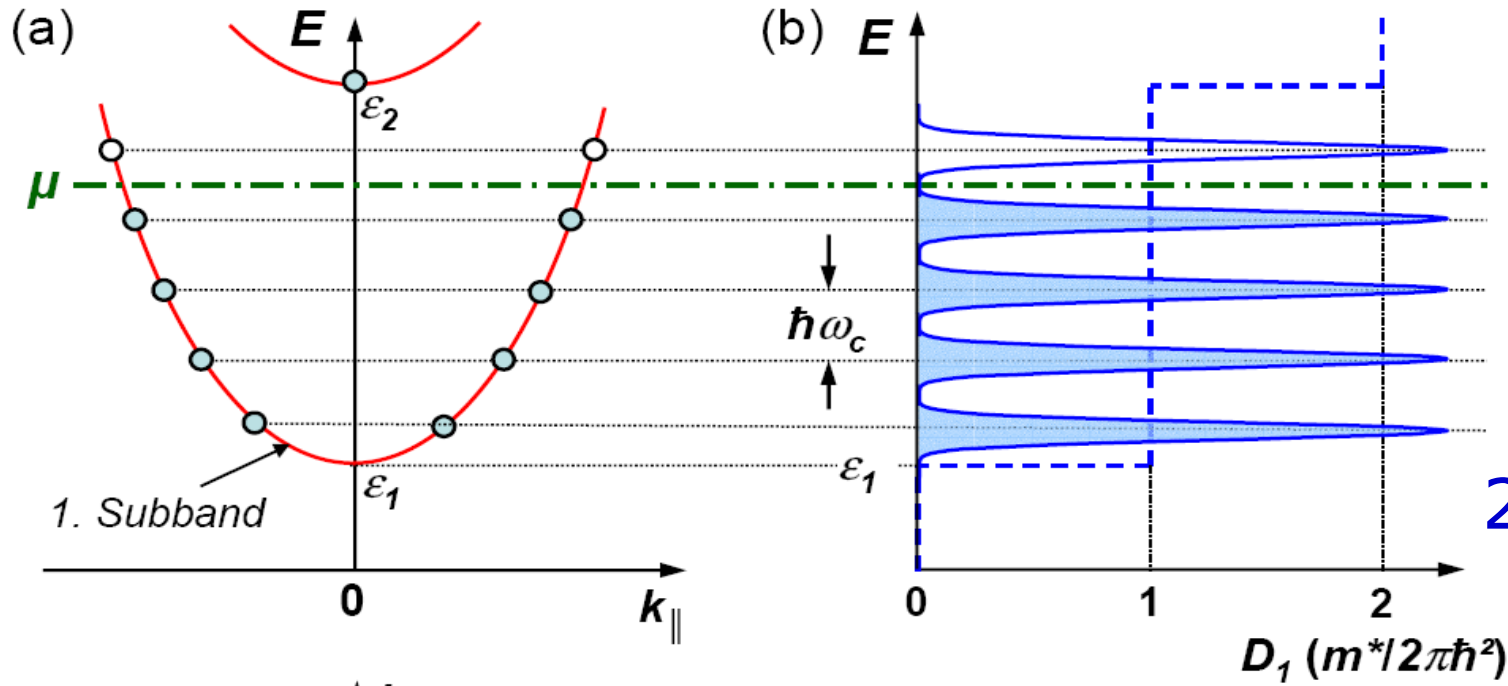
Nobelpreis 1985



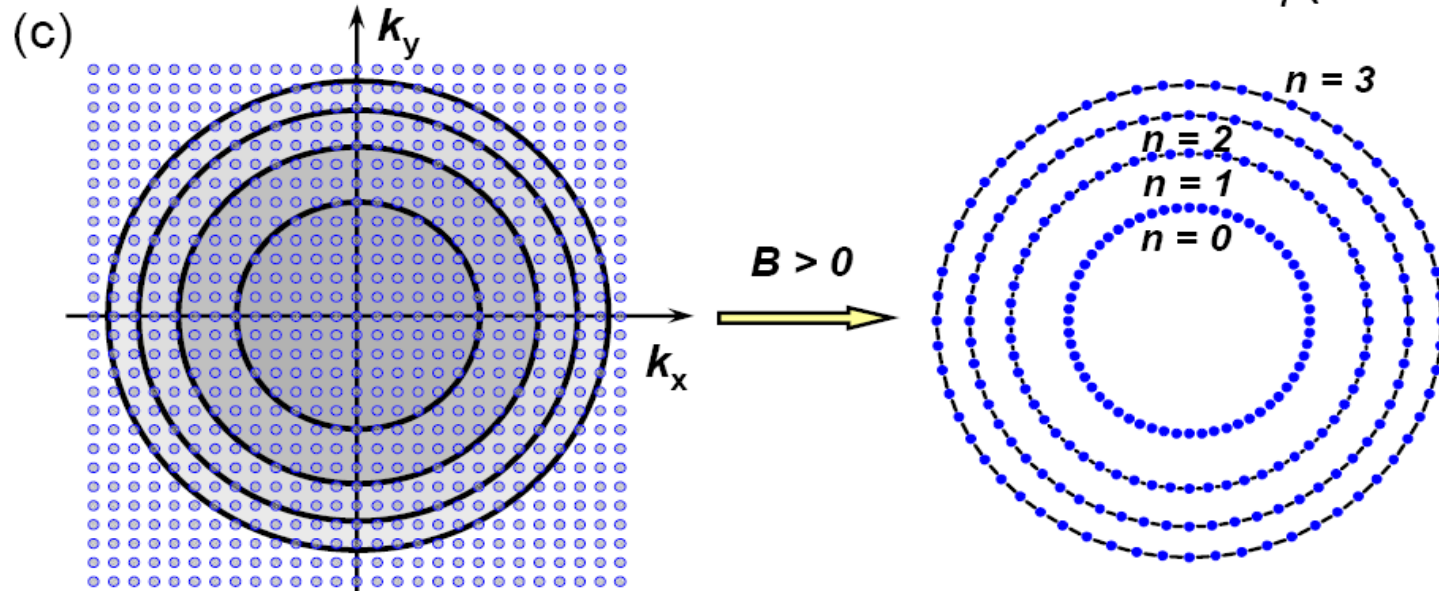
$$U_y = R_{xy} I_x$$

K. von Klitzing,  
G. Dorda,  
M. Pepper,  
Phys. Lett. **45**, 494 (1980)

# 2DEG in an external magnetic field



DOS:  
2D box  $\rightarrow$  peak



## Entartung des untersten Landauniveaus

alle Spins parallel

$n_l$  Zustände pro Fläche im Intervall  $\hbar\omega_c$

$$n_l = \frac{g_l}{L^2} = \hbar\omega_c D(B=0) = \hbar\omega_c \frac{m^*}{2\pi\hbar^2} = \hbar \frac{eB}{m^*} \frac{m^*}{2\pi\hbar^2} = \frac{e}{h} B$$

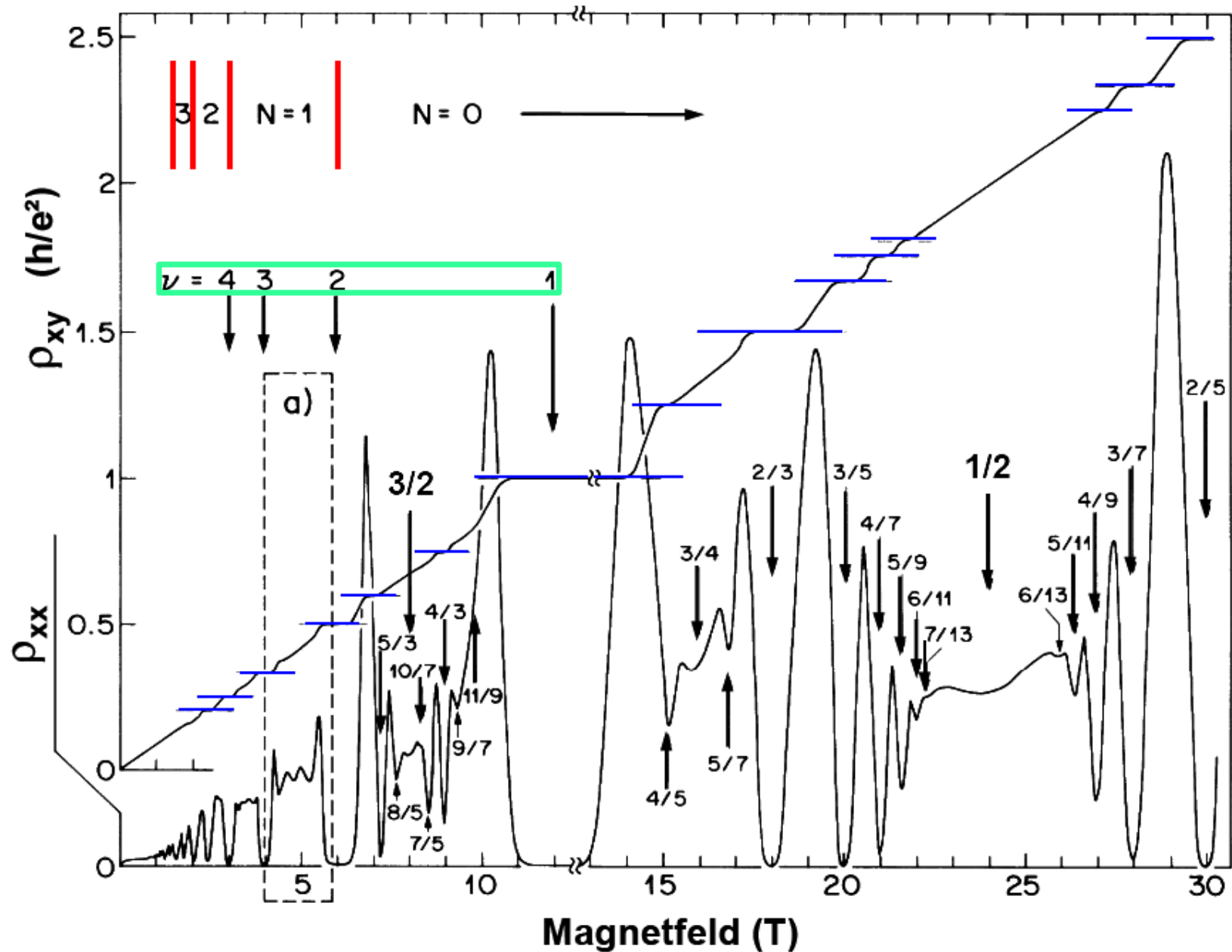
$$R_H = \frac{B}{ne} = \frac{B}{in_l e}$$

$i$  Zahl der Landauniveaux

$$\rightarrow R_H = \frac{h}{e^2} \frac{1}{i} = \frac{1}{i} R_K$$

$$R_K = \frac{h}{e^2} = 25812,807572(95)\Omega$$

wenig später: **Fraktionaler Quanten-Hall-Effekt**





# Nobel Lecture: The fractional quantum Hall effect

Horst L. Störmer, Rev. Mod. Phys. **71**, 875 (1999)



T. Kovacs, T. Duff, Bell Labs

Nobelpreis 1998

Störmer, Tsui, Laughlin



Linda A. Cicero /  
Stanford News Service

# Quantized conductance of point contacts in a 2DEG

B. J. van Wees et al., Phys. Rev. Lett. **60**, 848 (1988)

Ballistic point contacts, defined in the 2DEG of a GaAs-AlGaAs heterostructure

Conductance changes are quantized

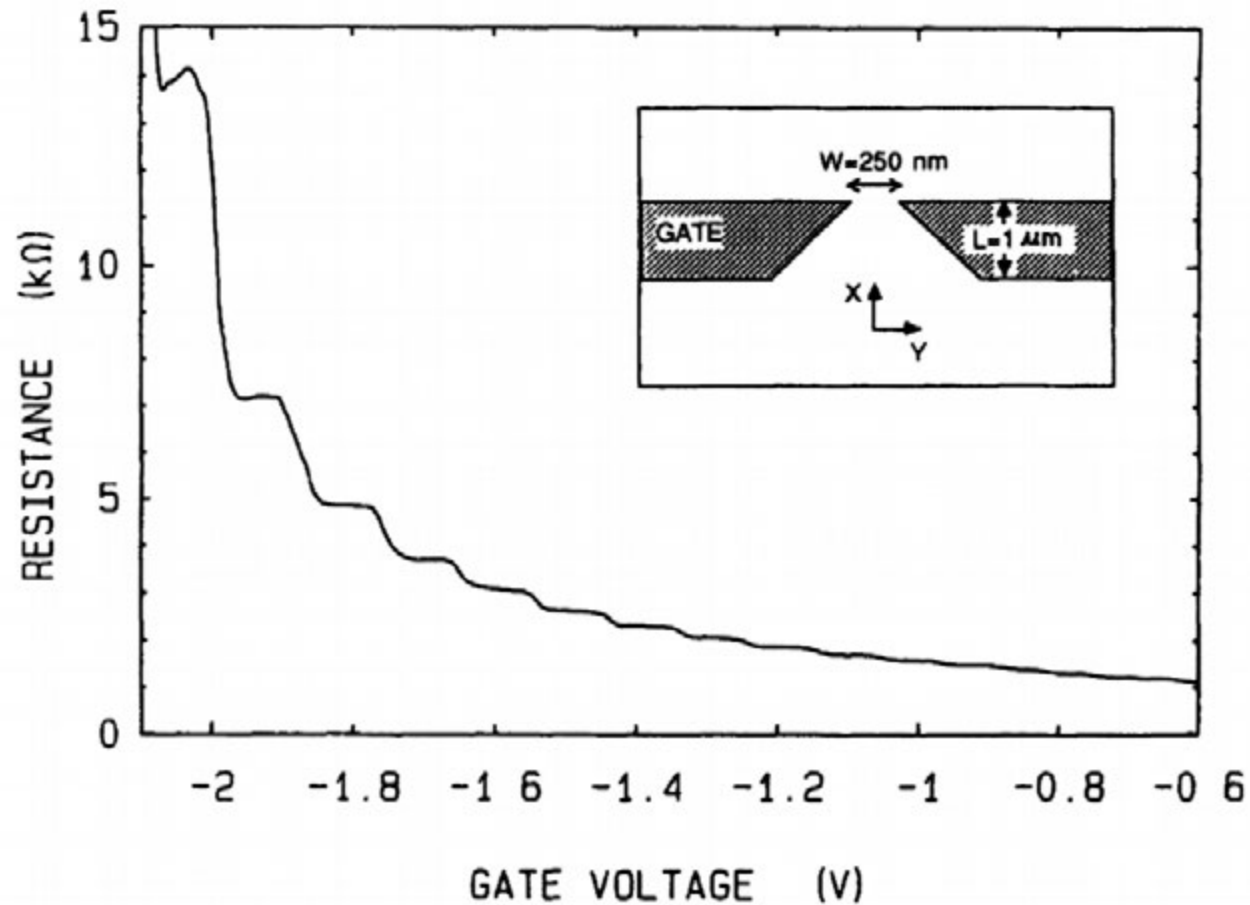


FIG. 1. Point-contact resistance as a function of gate voltage at 0.6 K. Inset: Point-contact layout.



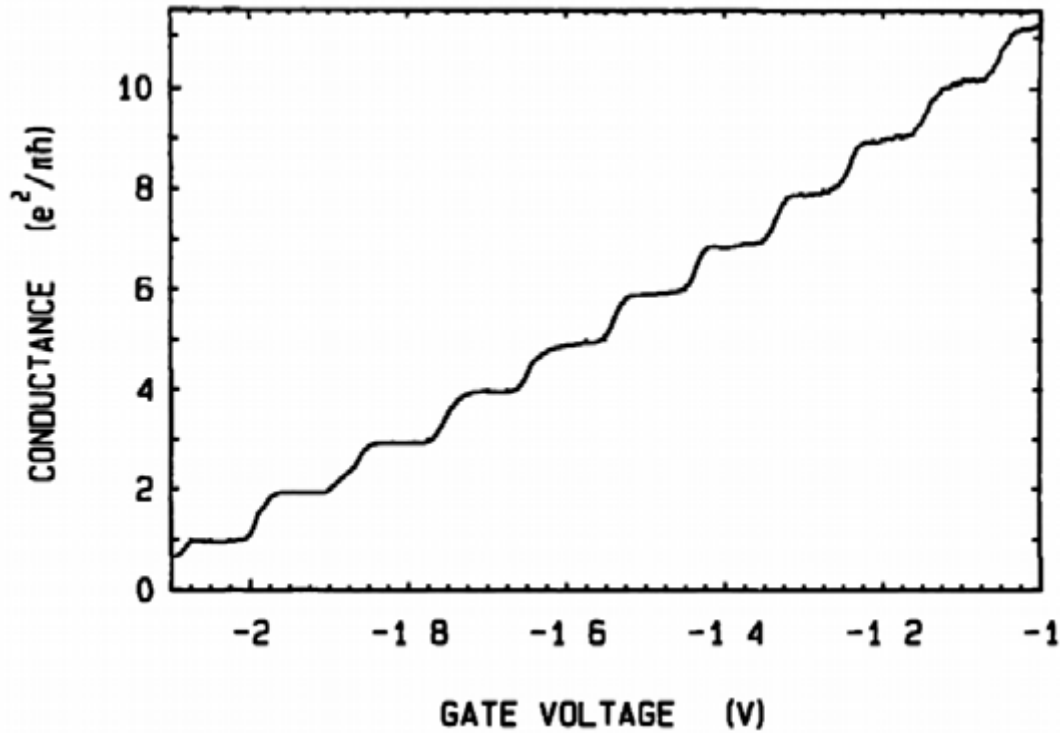


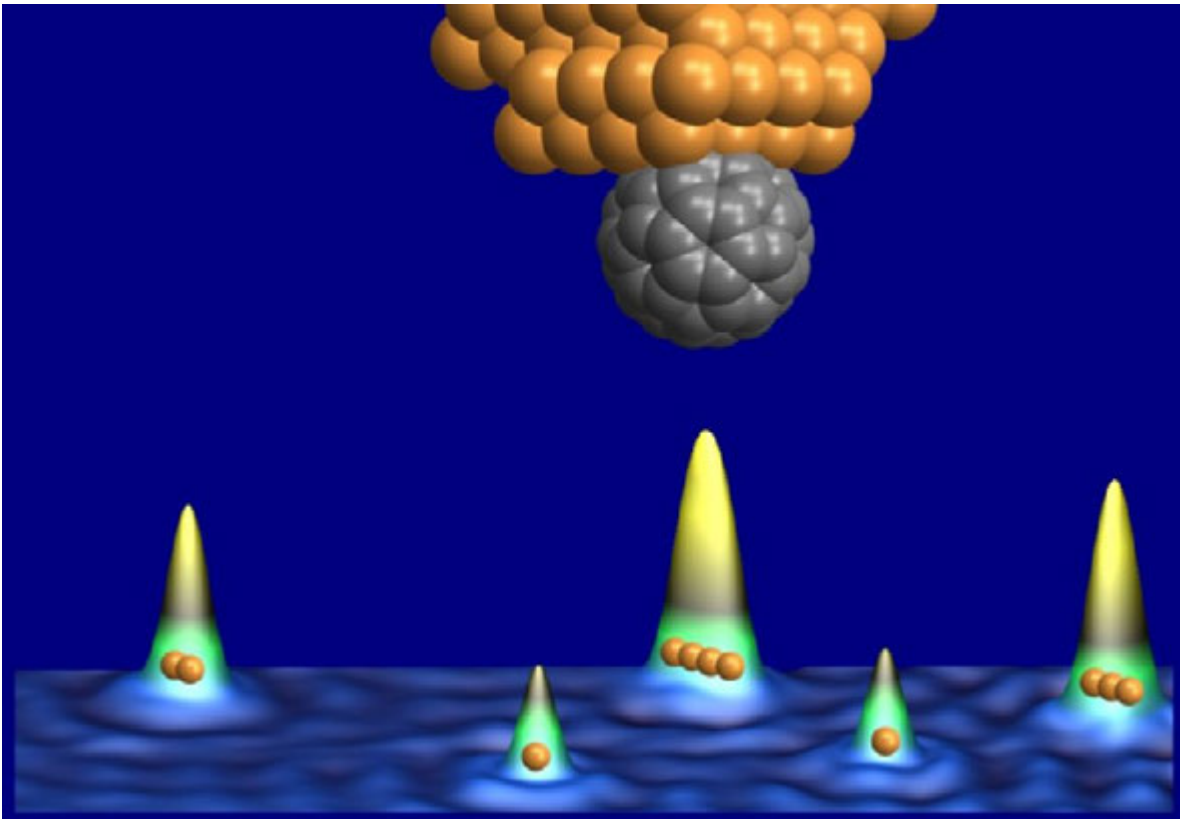
FIG. 2. Point-contact conductance as a function of gate voltage, obtained from the data of Fig. 1 after subtraction of the lead resistance. The conductance shows plateaus at multiples of  $e^2/\pi\hbar$ .

Landauerformel

$$G = \frac{e^2}{\pi\hbar} \sum_{n,m=1}^{N_c} |t_{nm}|^2$$

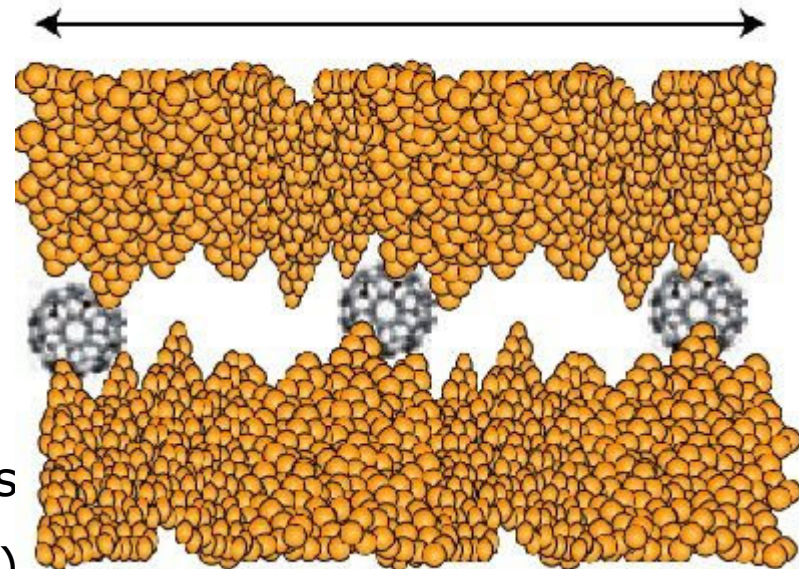
# Atomic-scale engineering of Cu electrodes

Schull, Frederiksen, Arnau, Sánchez-Portal, Berndt, Nature Nanotechnol. **6**, 23 (2011)



State-of-the-art  
e-beam lithography

(hardly used)  
22-nm-wide contact



From A. Heinrich, Closing in on molecular junctions  
Nature Nanotechnol. (news & views) **6**, 7 (2011)